

FIG. 1

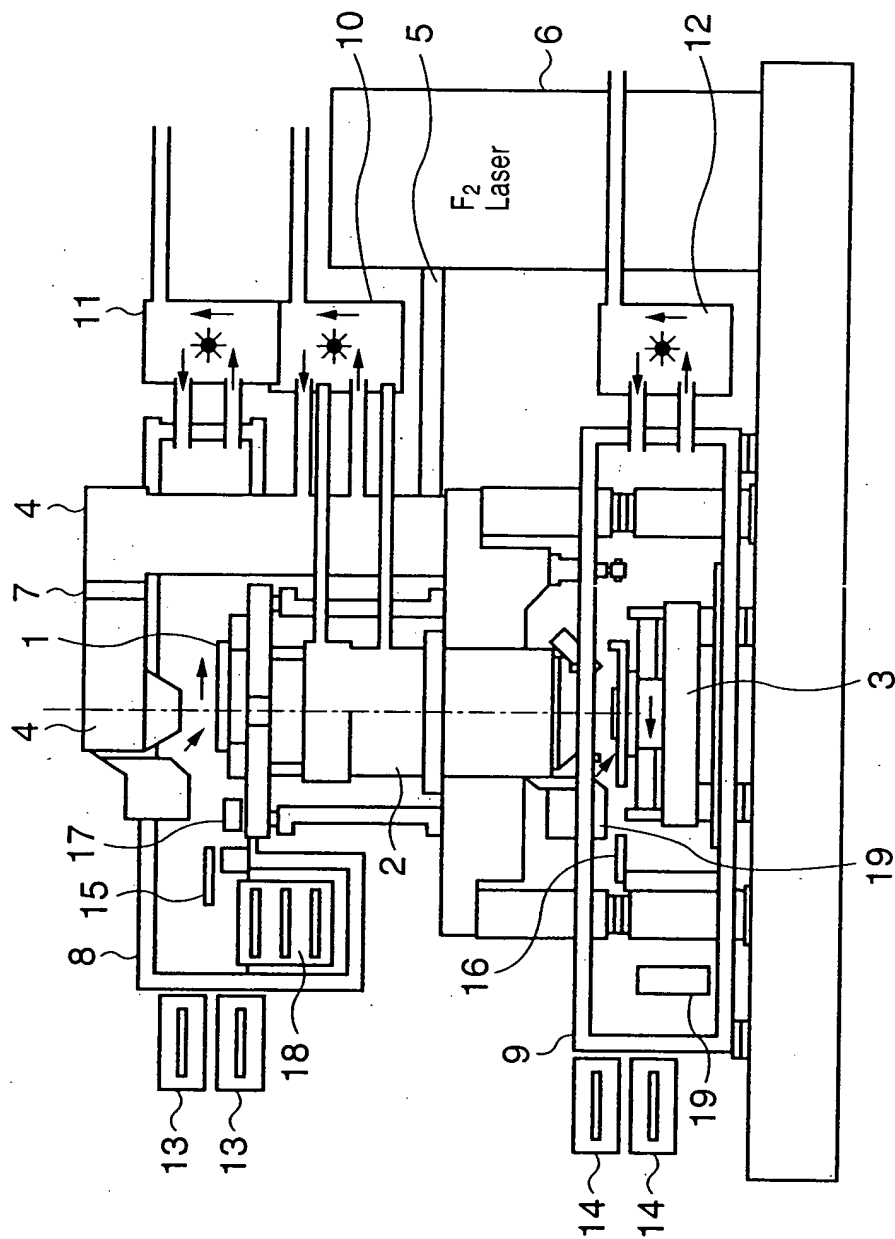


FIG. 2

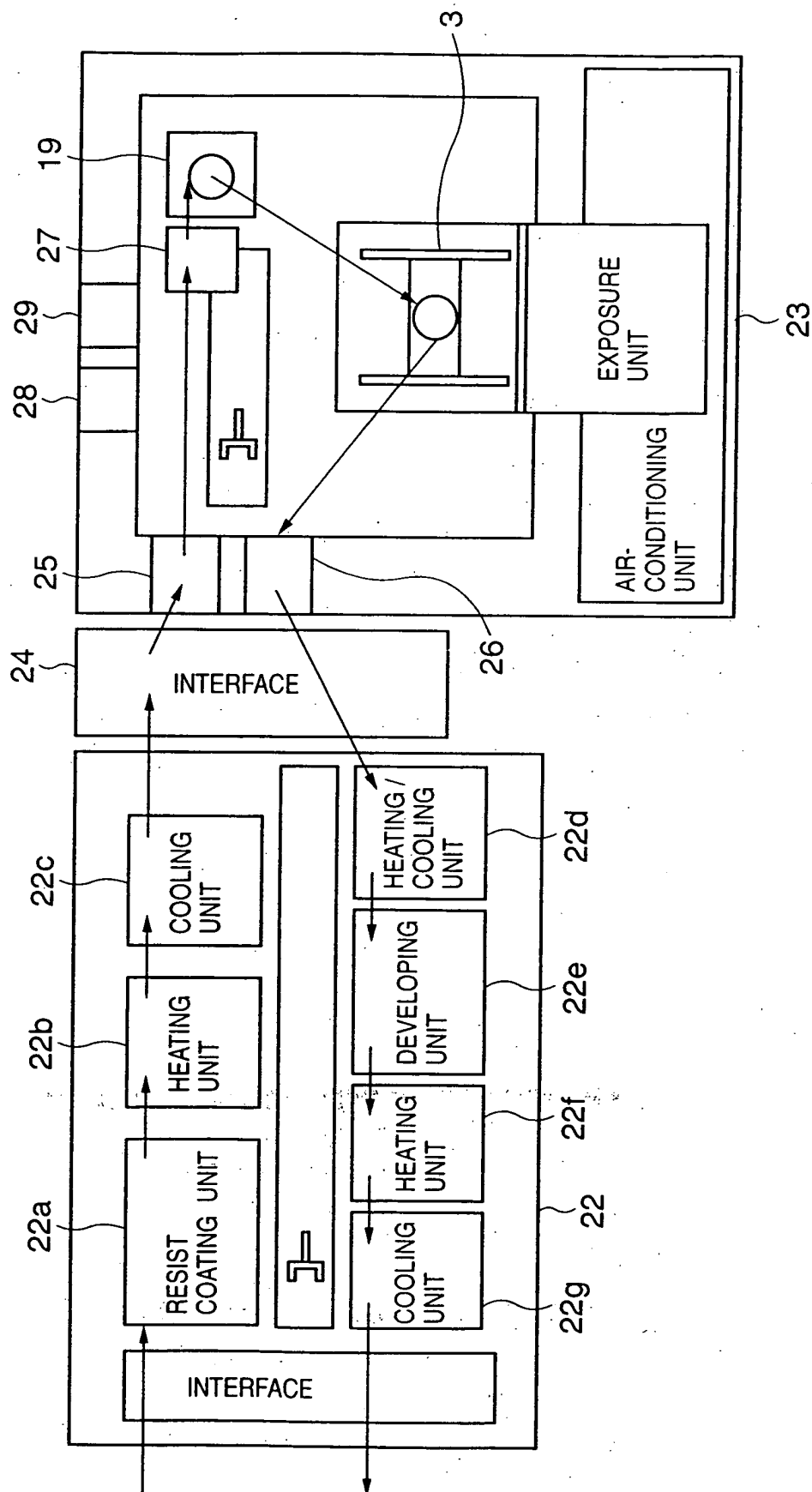
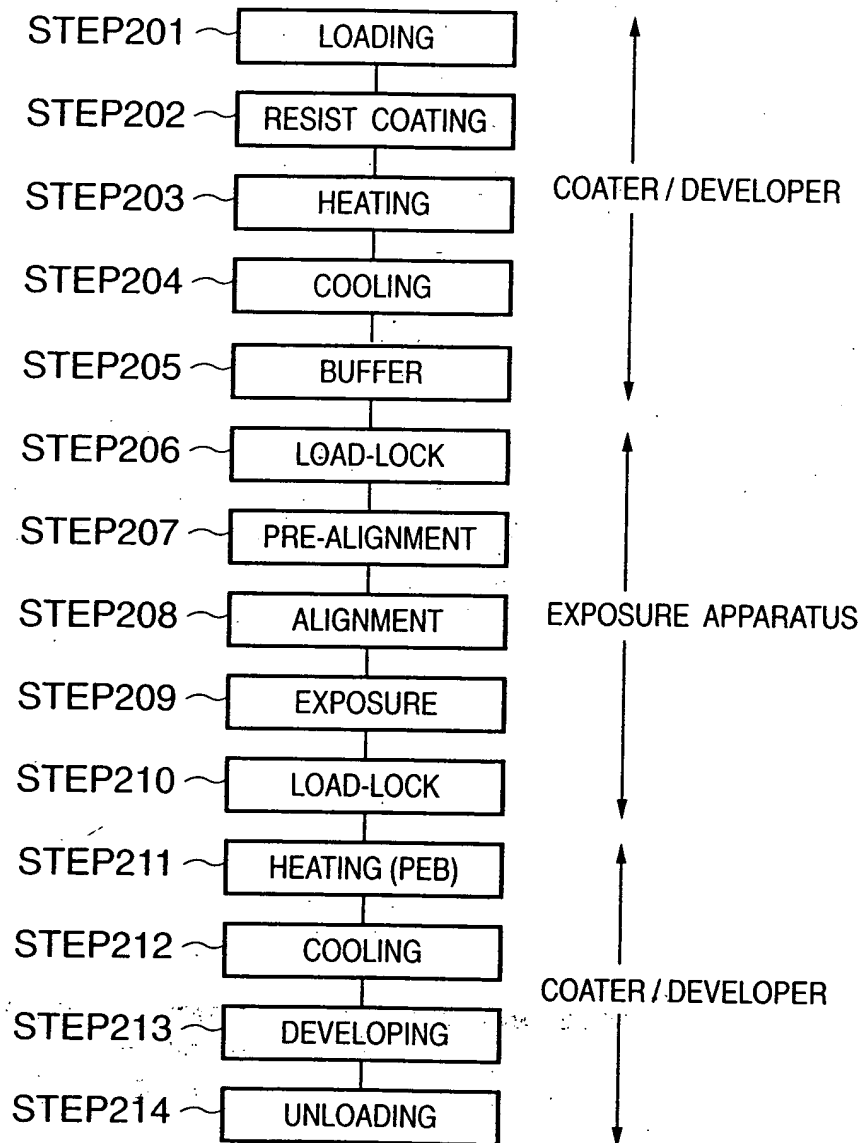


FIG. 3

F05250-60E49860

FIG. 4

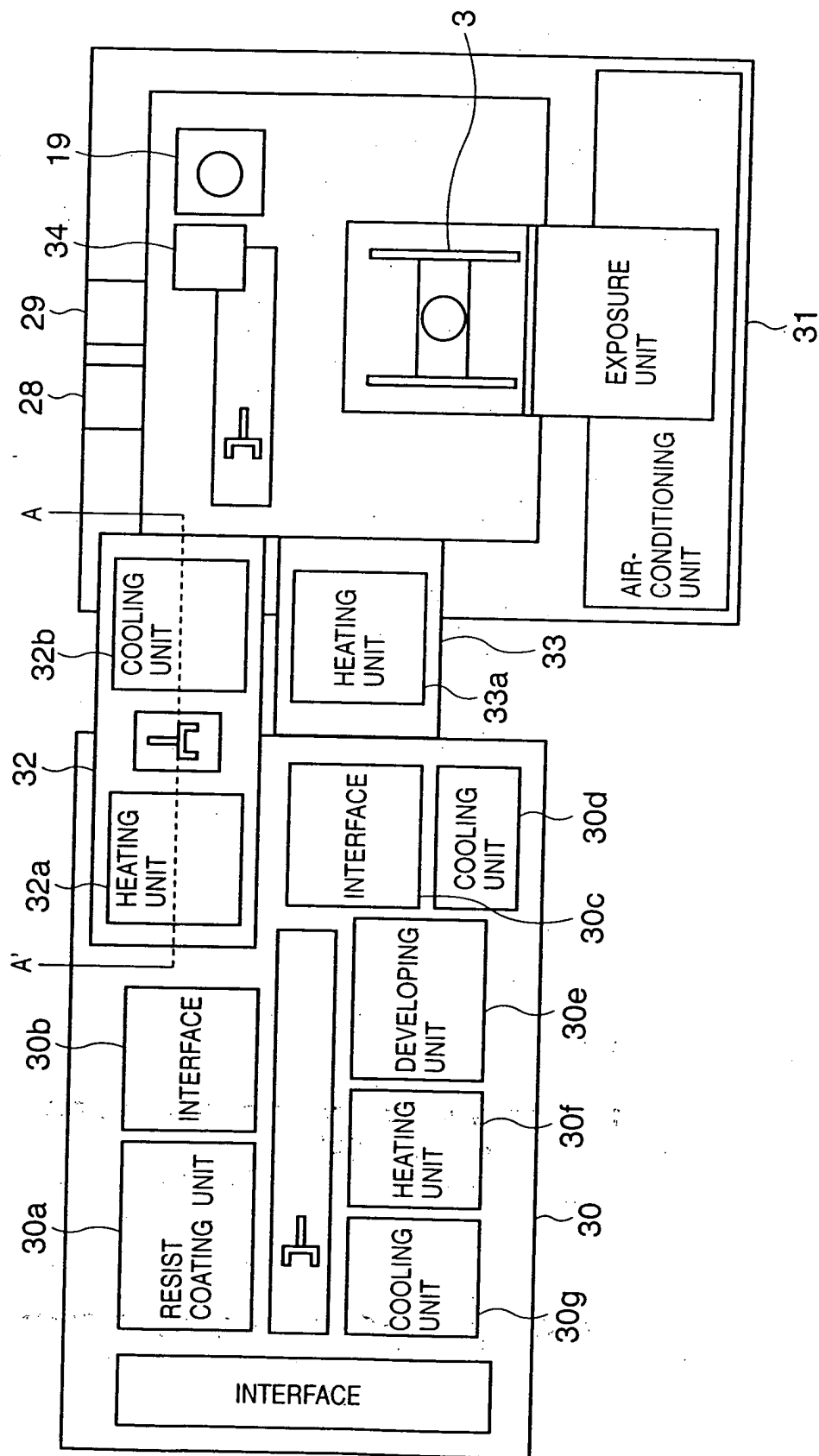


FIG. 5

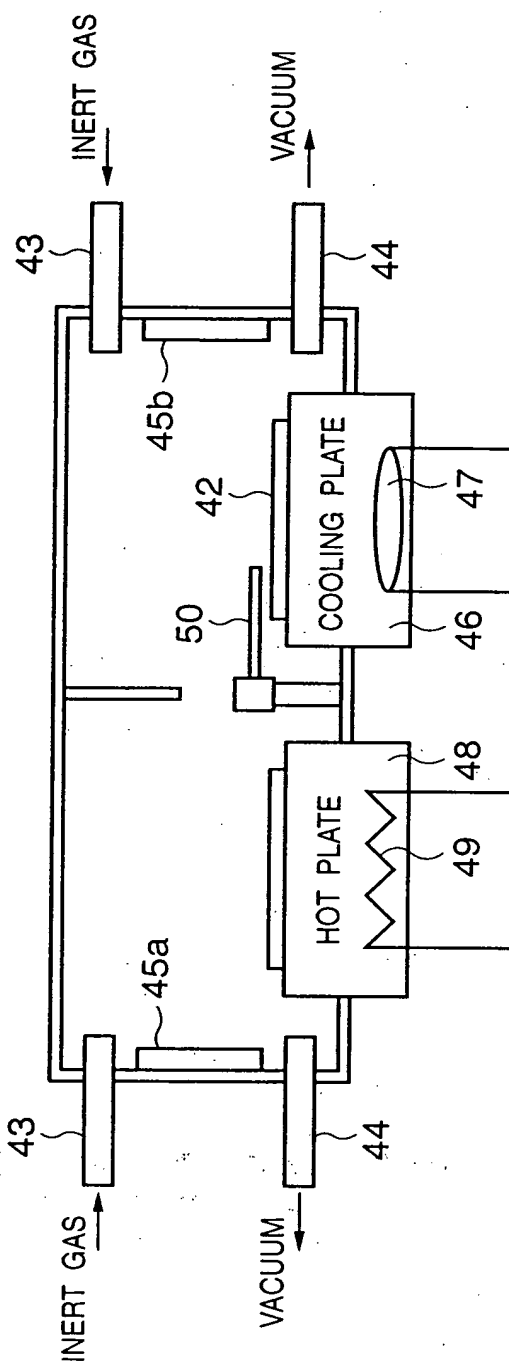


FIG. 6

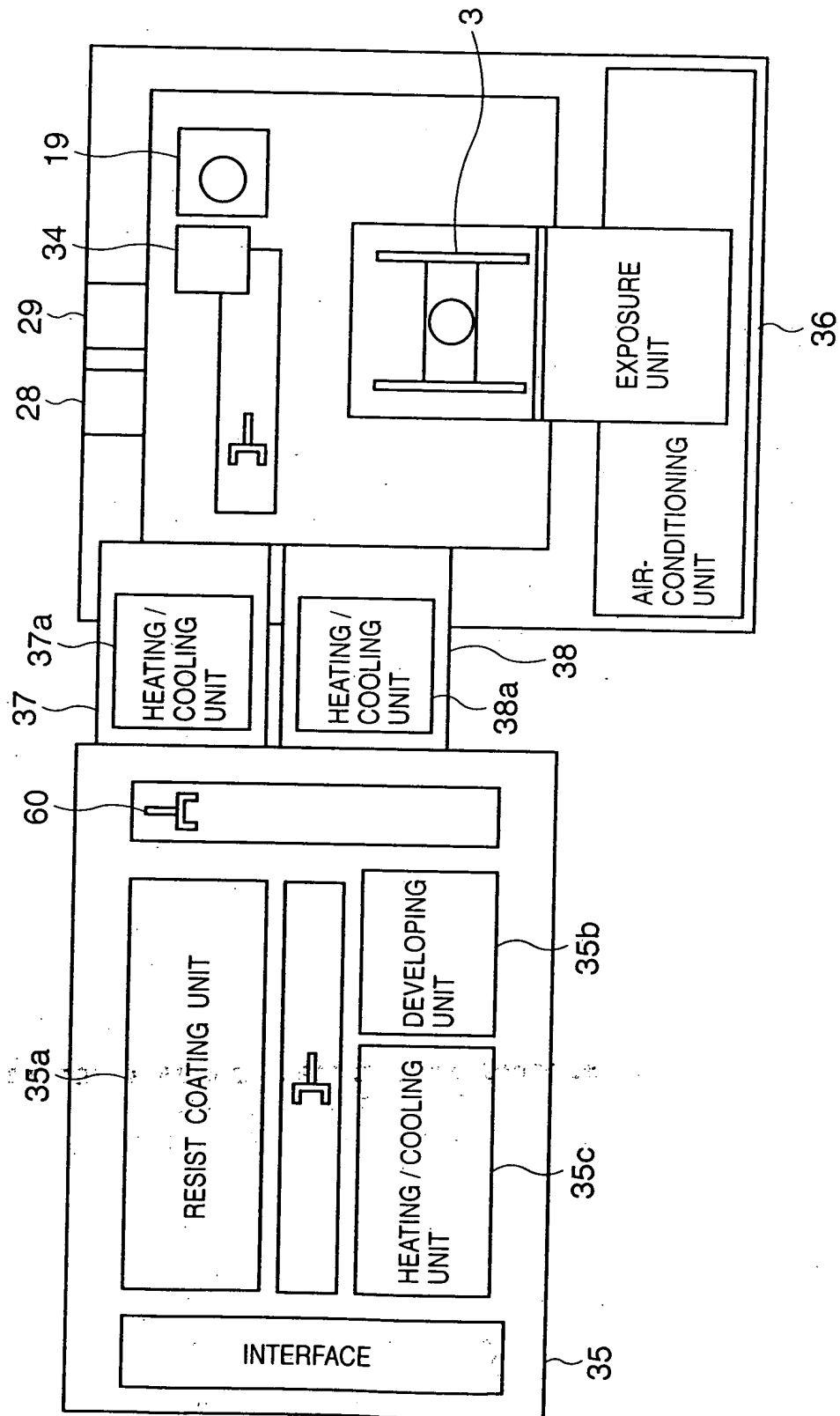


FIG. 7

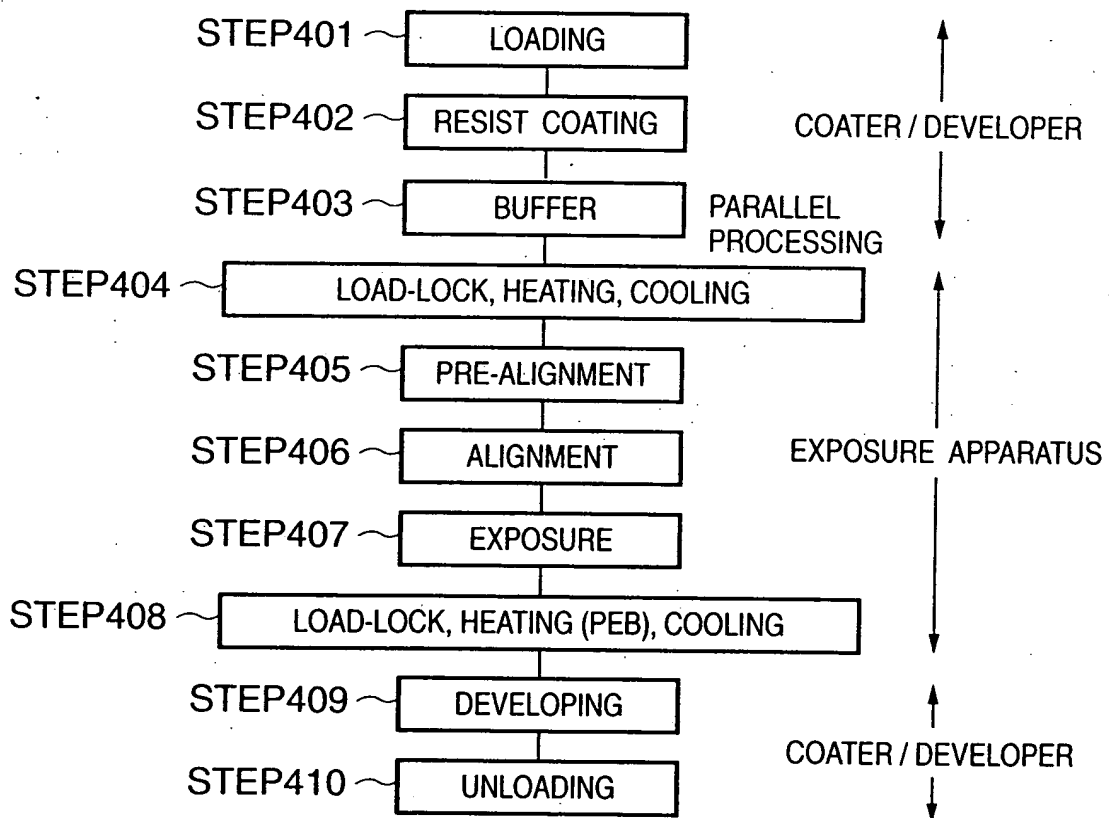
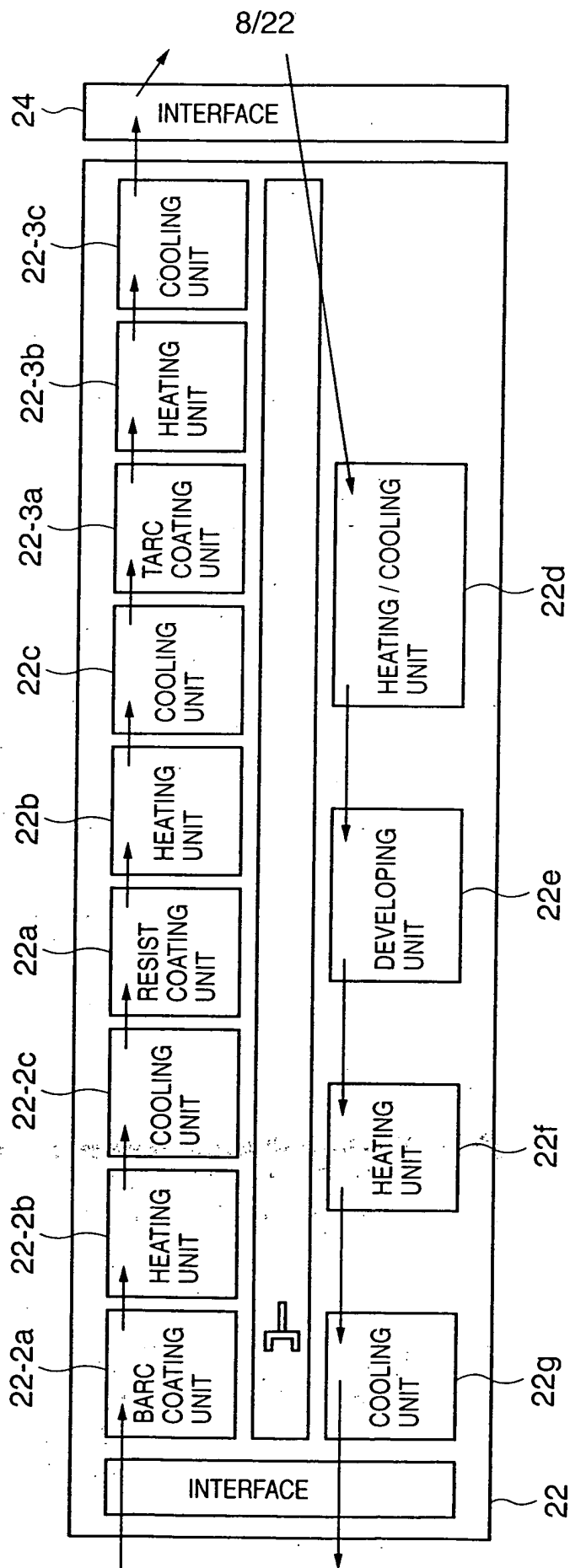
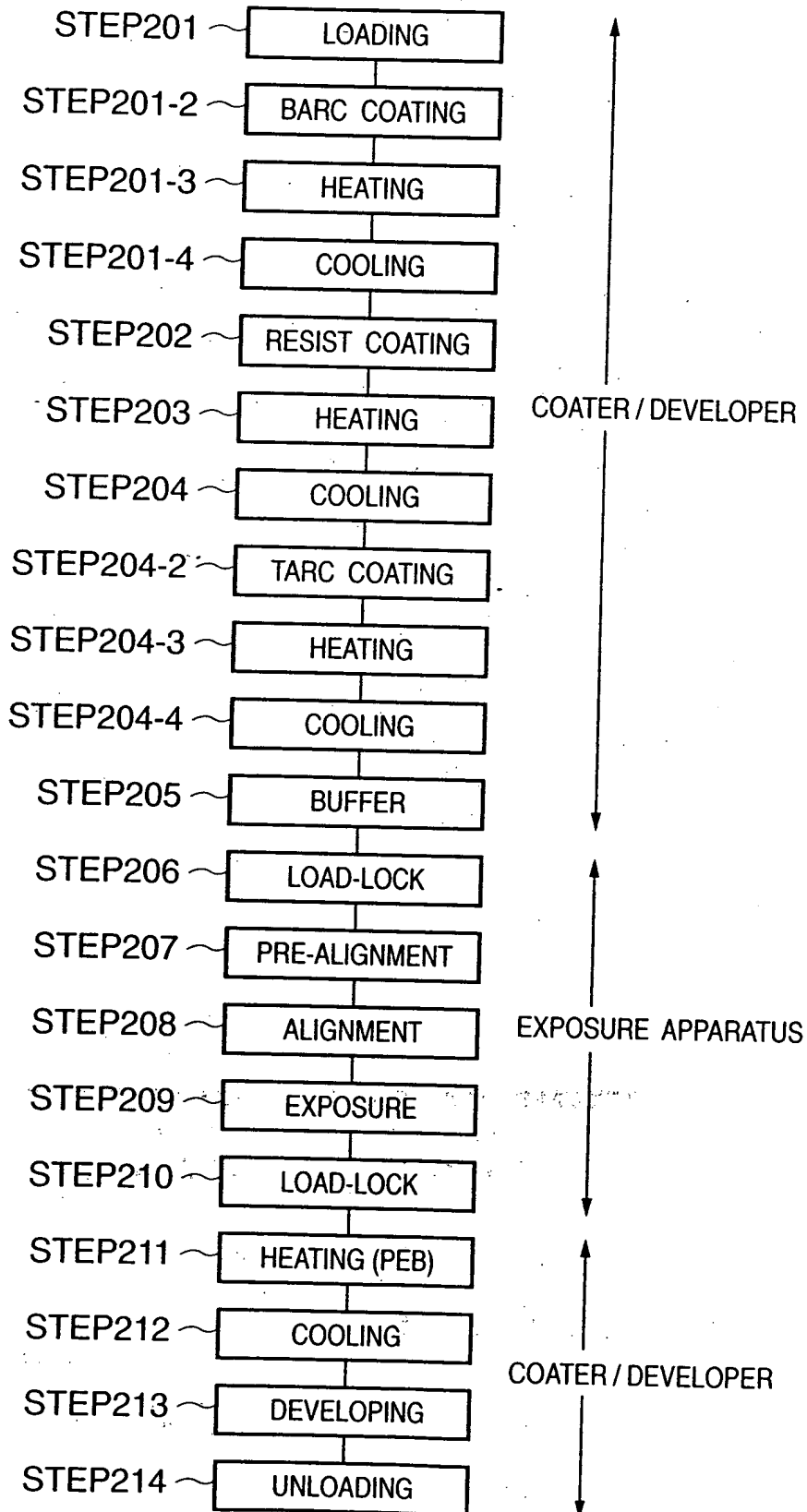


FIG. 8



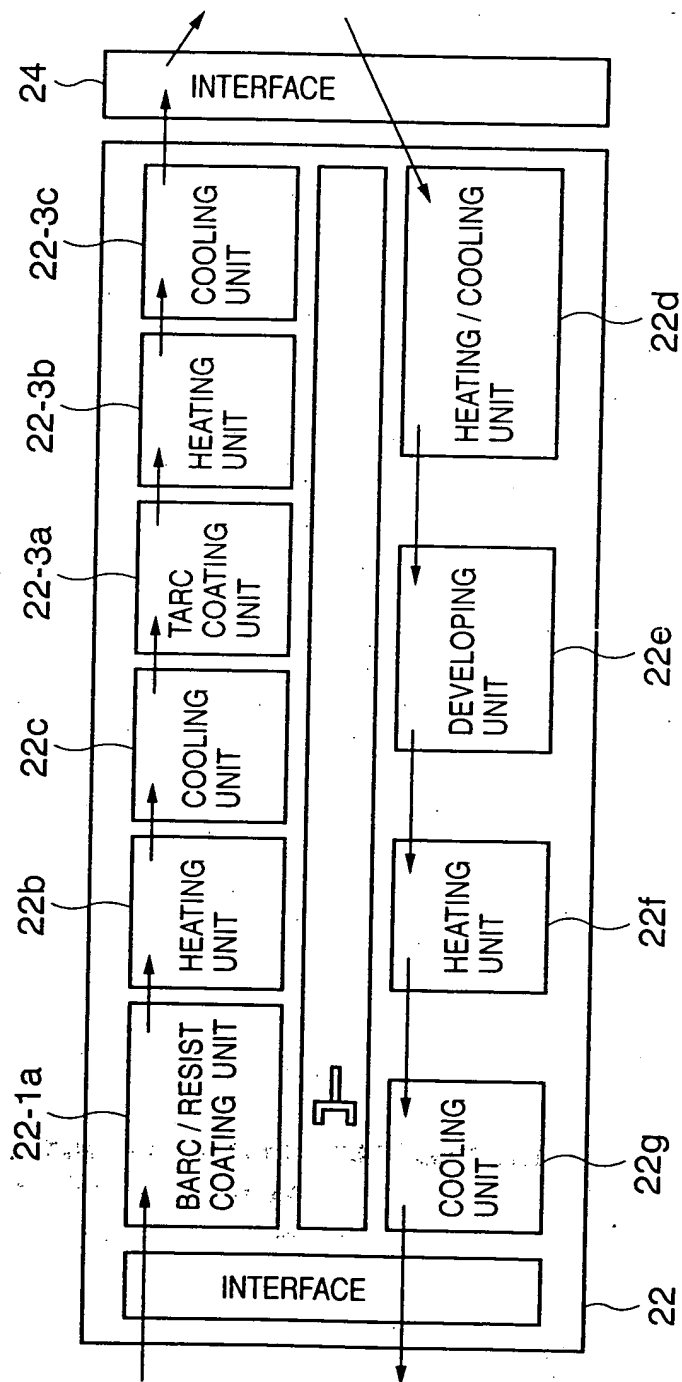
9/22

FIG. 9



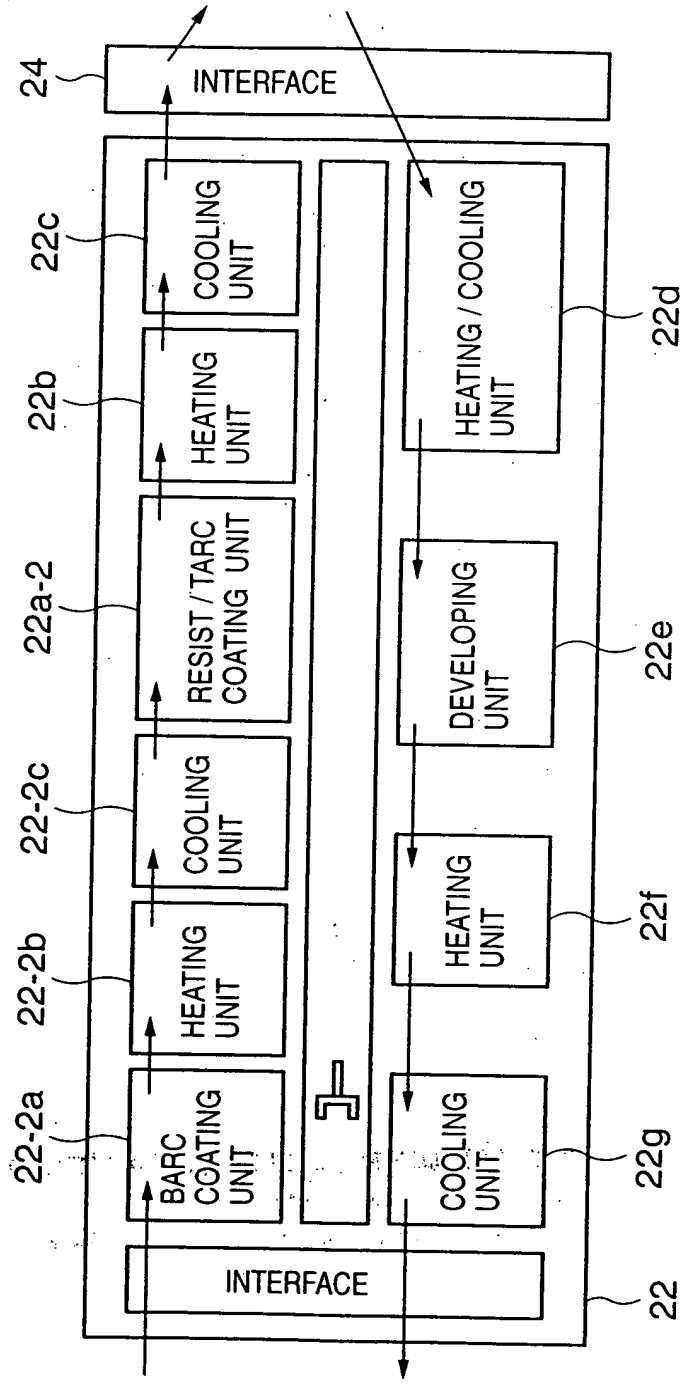
FO5250" 60E49860

FIG. 10



FO5250' 60E49860

FIG. 11



FOSSO-60E49860

FIG. 12

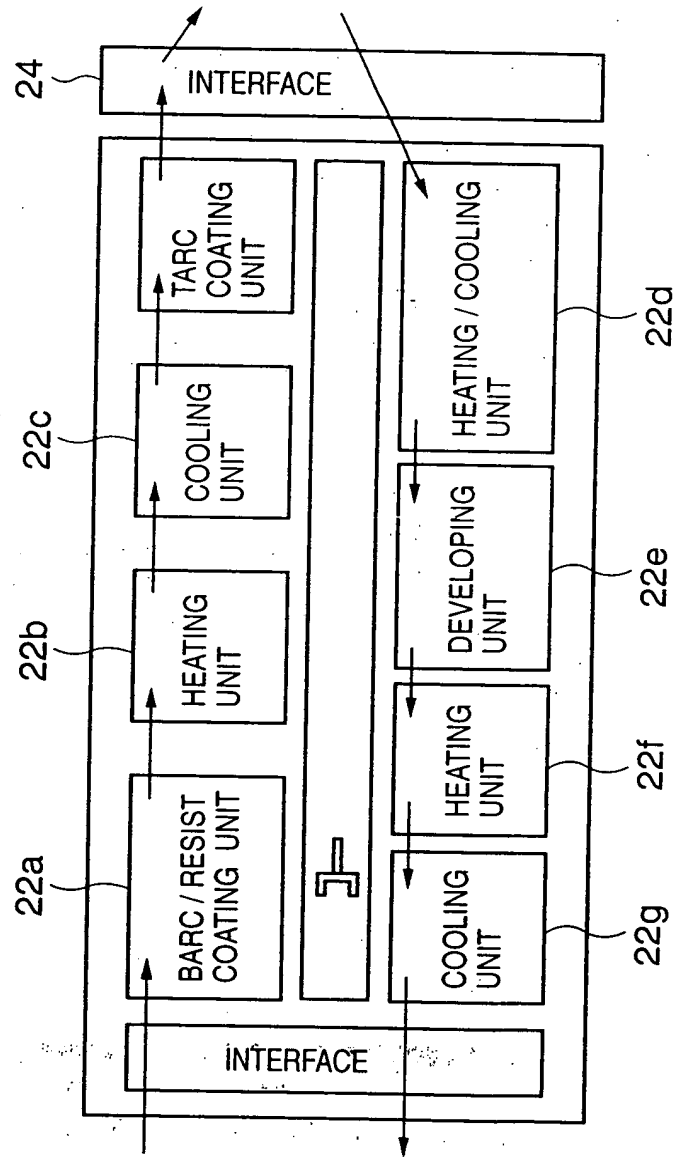


FIG. 13

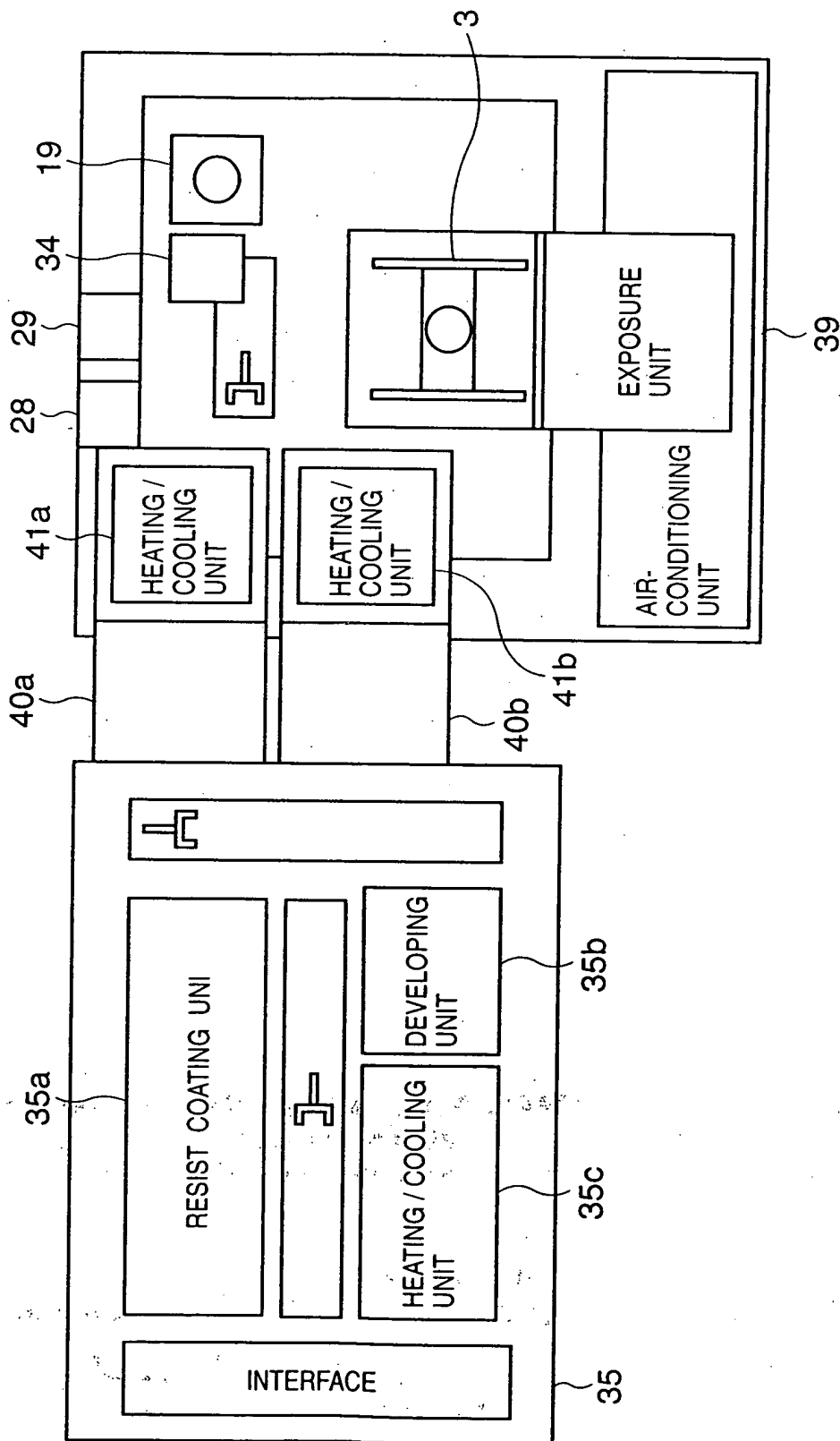
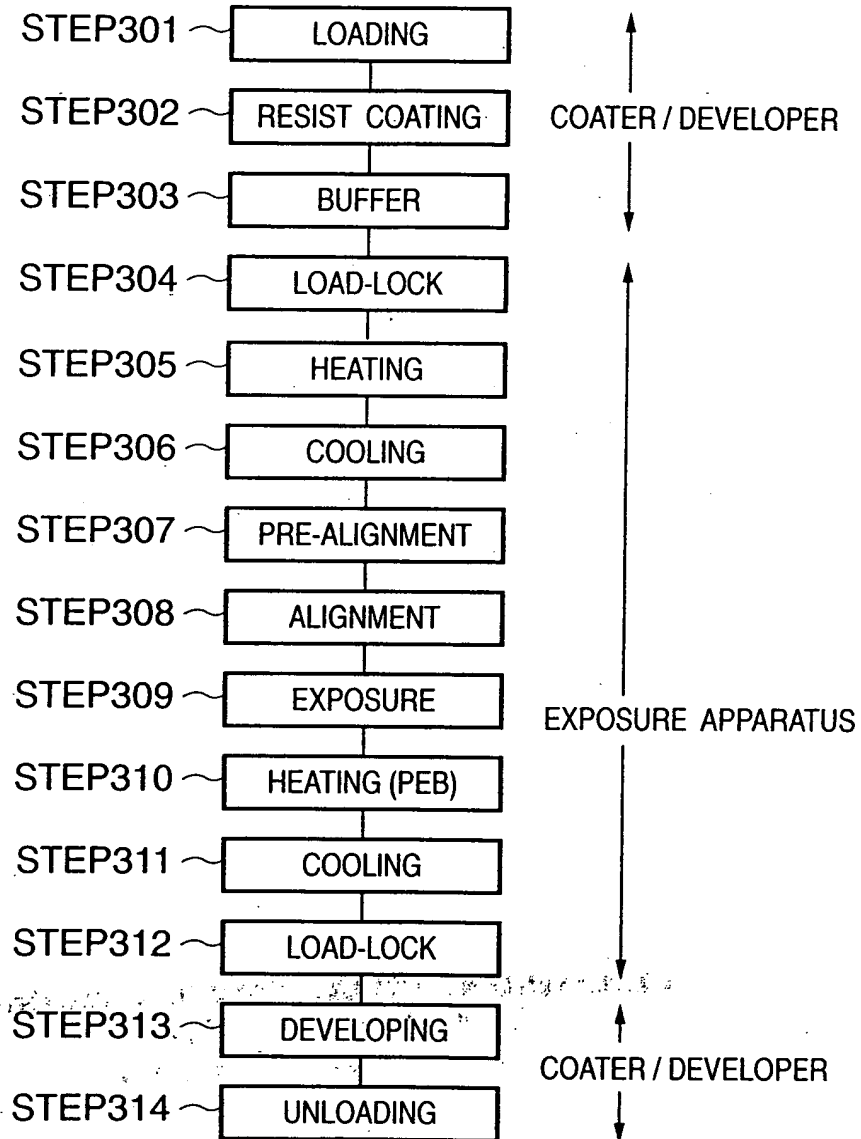


FIG. 14

FD5250-60E49860

The diagram illustrates a laser-based lithography system. At the top, an F_2 Laser (10) emits a beam (5) through a series of mirrors and lenses (1, 2, 3, 4, 6, 7) onto a substrate (19). The substrate is mounted on a stage (14) with a focus mechanism (13). A detector (18) is positioned to monitor the beam. The system is housed in a chamber (20).

FIG. 16

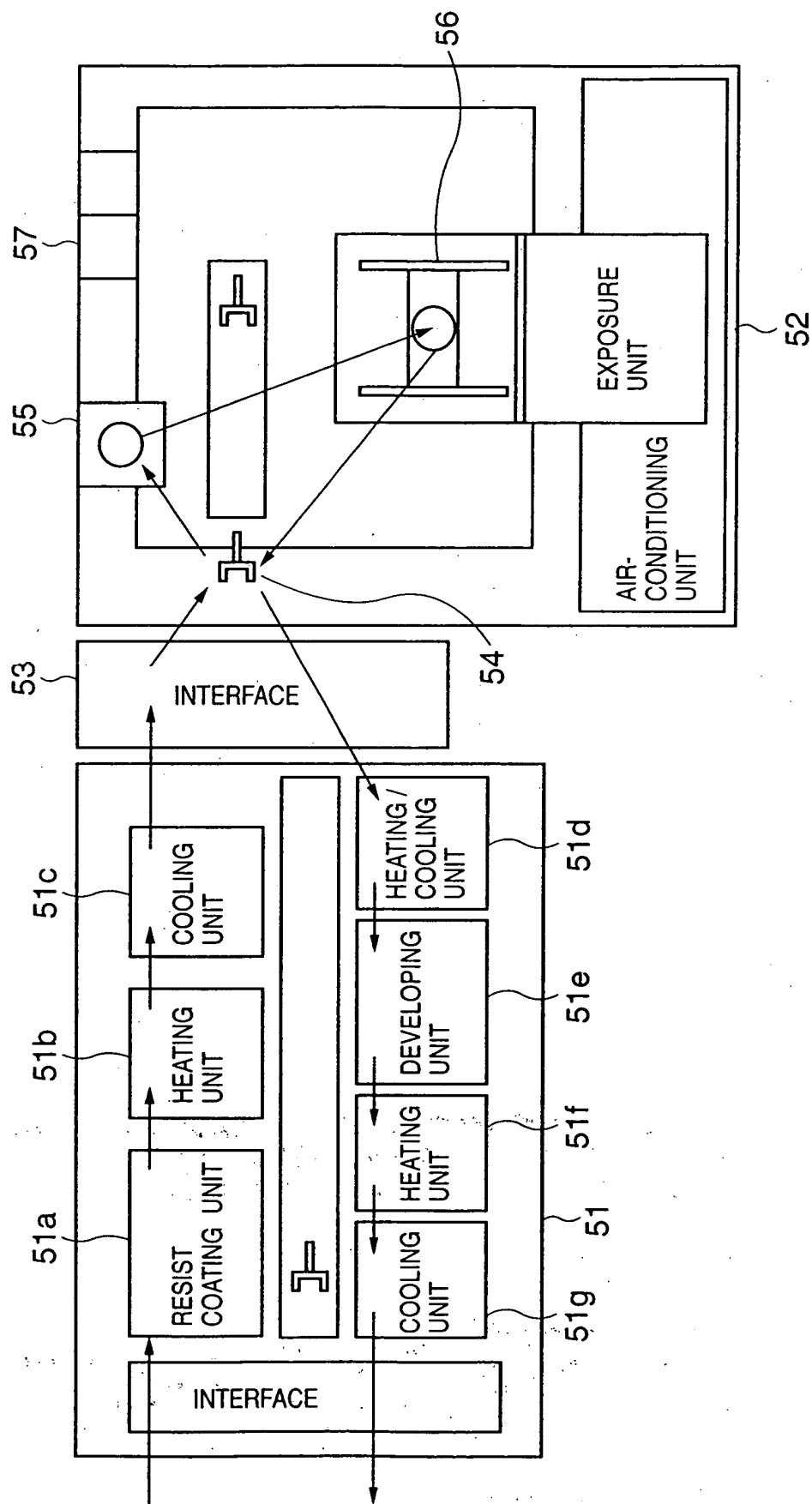


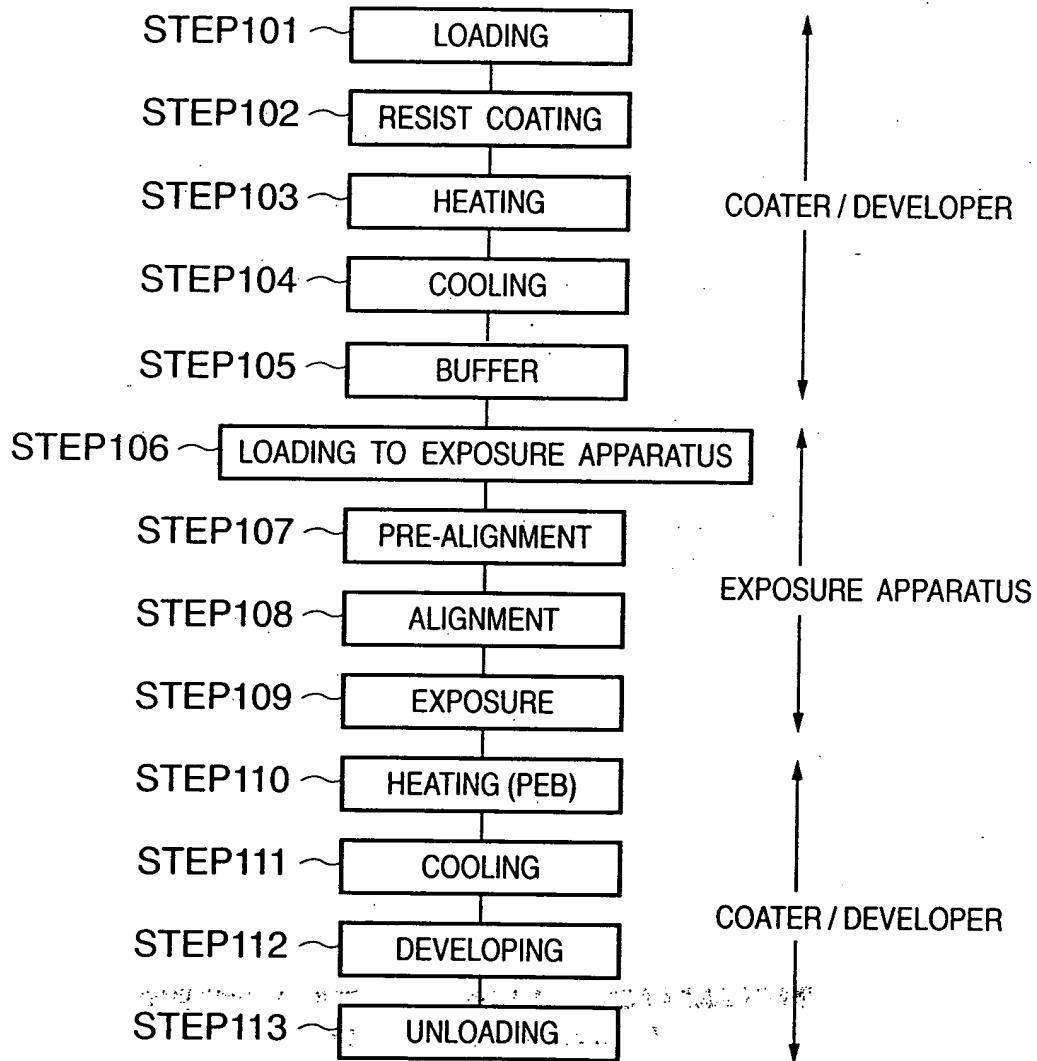
FIG. 17

FIG. 18

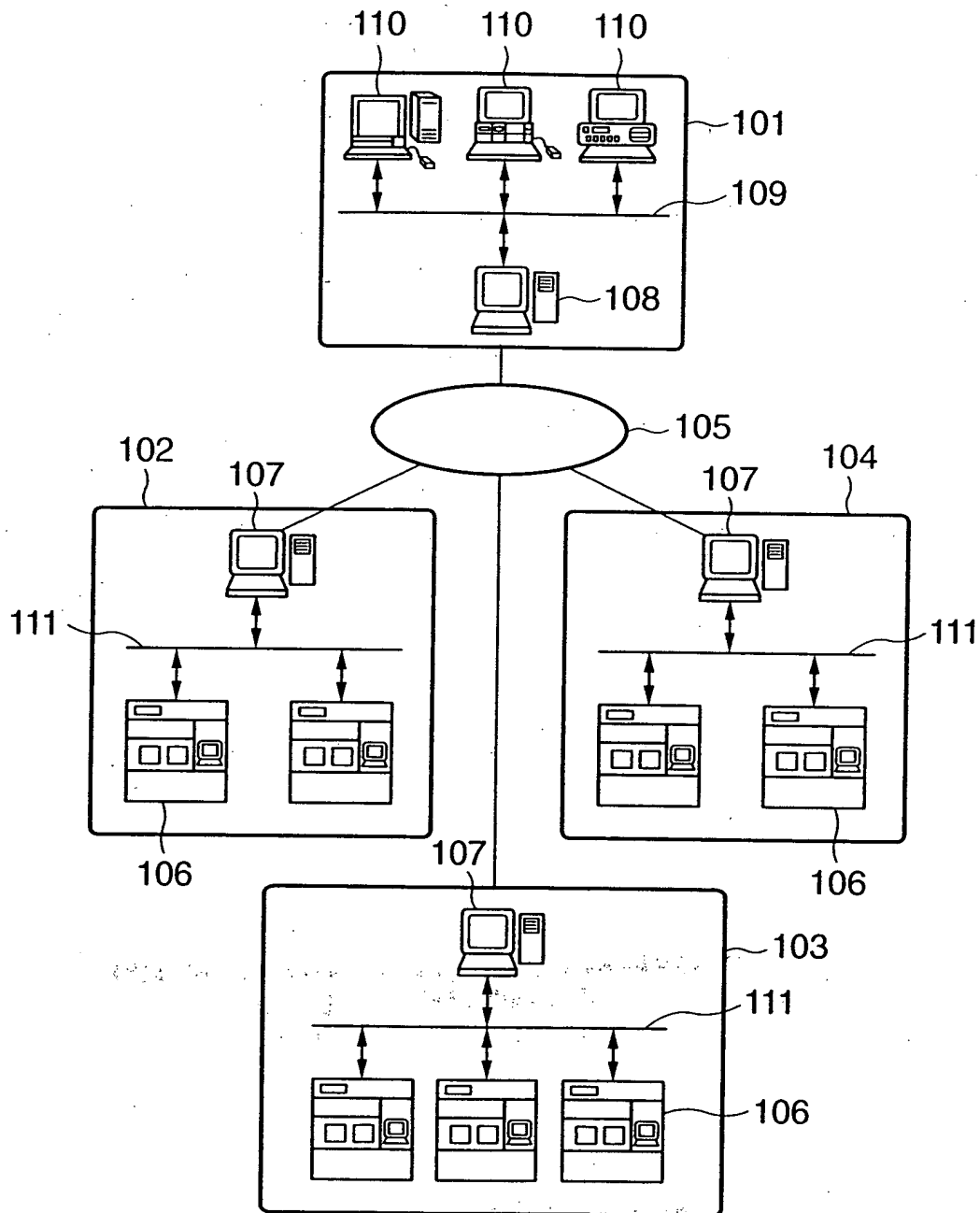
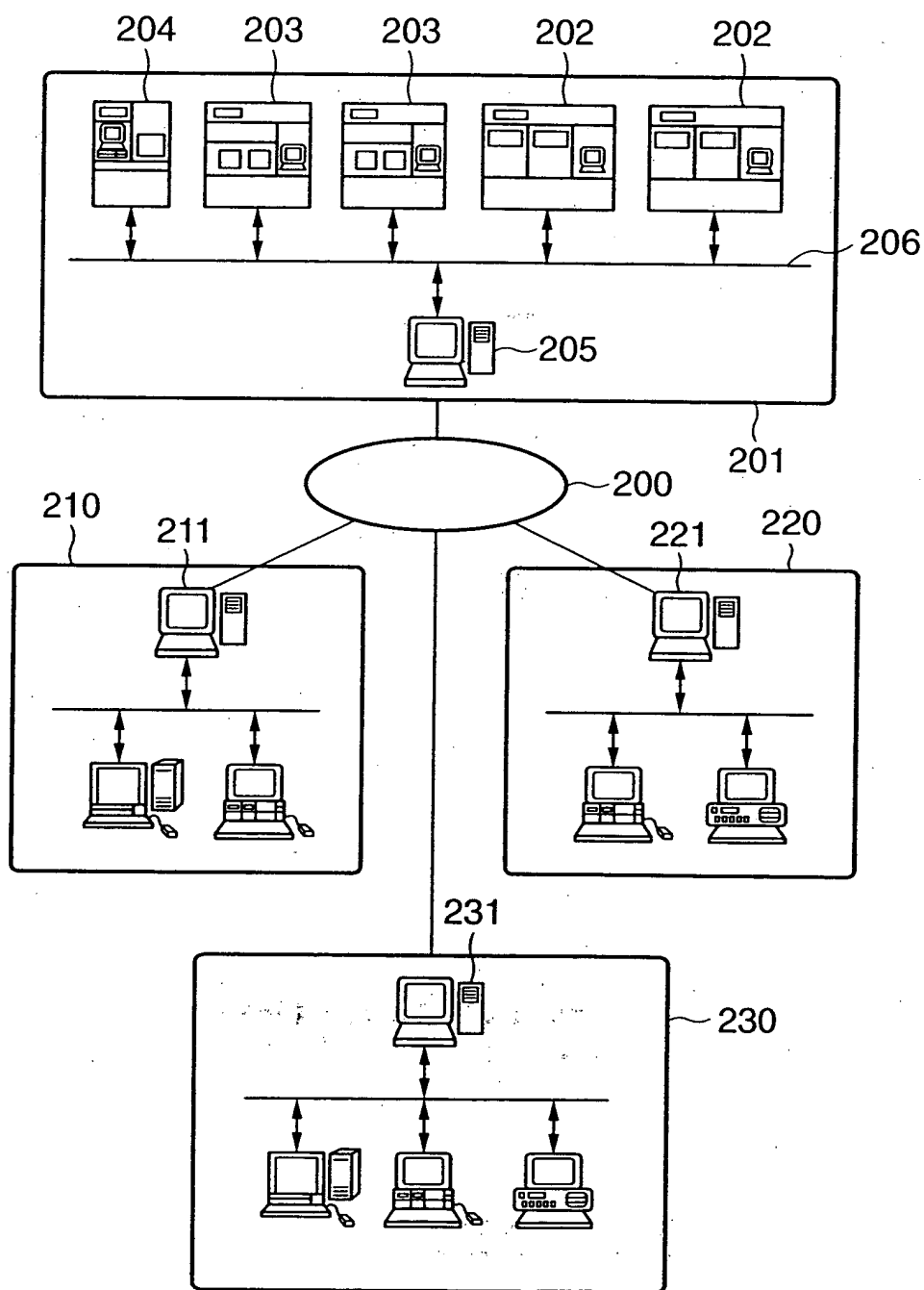


FIG. 19



FO5250" 60E49860

FIG. 20

URL

TROUBLE DB INPUT WINDOW

OCCURRENCE DATE ~ 404

TYPE OF APPARATUS ~ 401

SUBJECT ~ 403

SERIAL NUMBER S/N ~ 402

DEGREE OF URGENCY ~ 405

SYMPTOM ~ 406

REMEDY ~ 407

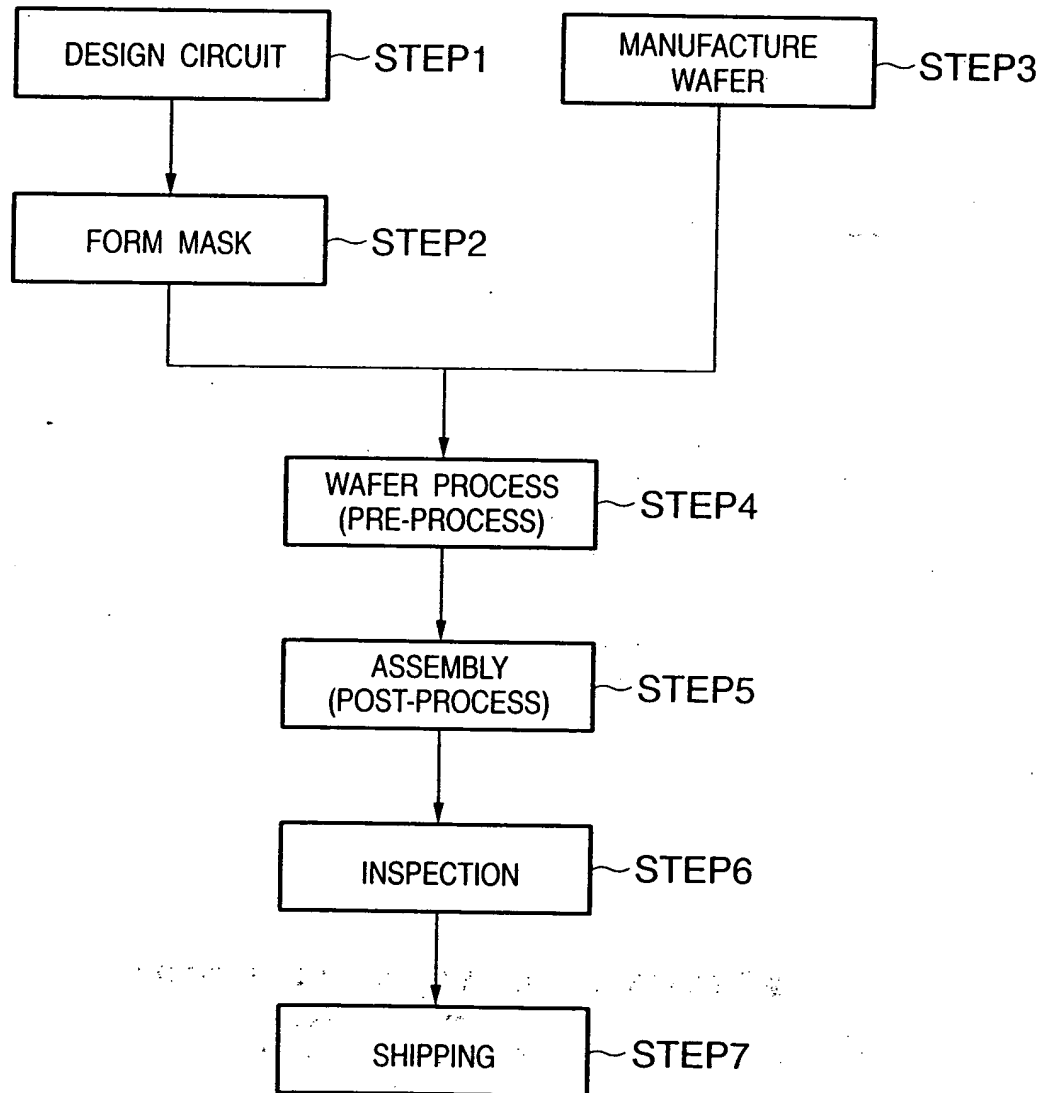
PROGRESS ~ 408

410 411 412

LINK TO RESULT LIST DATABASE SOFTWARE LIBRARY OPERATION GUIDE

F05250-00E49860

FIG. 21



SEMICONDUCTOR DEVICE MANUFACTURING FLOW

T05250 60E49860

FIG. 22

